

ABSTRACT

METHODS FOR CONTROLLING SPREAD OF IMPRINT MATERIAL

A substrate useful for imprint lithography having a location thereon defining an imprint field, the imprint field further defined by an interior region, a perimeter region surrounding the interior region, and a border, with the perimeter region further including fluid control features. A polymerizable material deposited on the substrate at the imprint field location is allowed to spread on the substrate, with the fluid control relief features redirecting the spreading of the polymerizable material so as to minimize spreading of the polymerizable material beyond the imprint field border as further imprint lithography techniques are then performed.

< Figure 7C >